



<b>Session Title:</b>	<b>[WD2] Atomic Layer Etching/Damage-Free Etching</b>
<b>Session Date:</b>	<b>November 22 (Wed.), 2023</b>
<b>Session Time:</b>	<b>10:20-11:30</b>
<b>Session Room:</b>	<b>Room D (Grand Ballroom 3, 2F)</b>
<b>Session Chair:</b>	<b>Dr. Hyeong-U Kim (KIMM, Korea)</b>

**[WD2-1]** **10:20-10:40**

**Layer-By-Layer Etching of 2 Dimensional Palladium Diselenide**

Ji Eun Kang, Seung Yup Choi, Ye Ji Shin, Hye Won Han, Ji Min Kim, and Geun Young Yeom  
(Sungkyunkwan Univ., Korea)

**[WD2-2]** **10:40-11:00**

**Ultra-Low Electron Temperature (ULET) Plasma for Damage-Free Plasma Processing**

Min-Seok Kim, Junyoung Park, Jiwon Jung, and Chin Wook Chung (Hanyang Univ., Korea)

**[WD2-3] [Invited]** **11:00-11:30**

**Plasma-Enhanced Atomic Layer Etching for Metals and Dielectric Materials**

Heeyeop Chae (Sungkyunkwan Univ., Korea)